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Sheet 1 of 5
Applicant: Bera, et al.
Title: APPARATUS FOR CONTROLLING
GAS FLOW IN A SEMICONDUCTOR
SUBSTRATE PROCESSING CHAMBER
Docket: 8549/ETCH/DRIE/JB1

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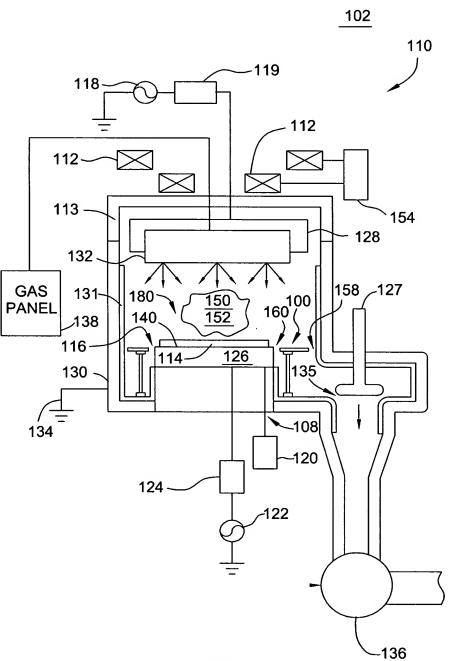


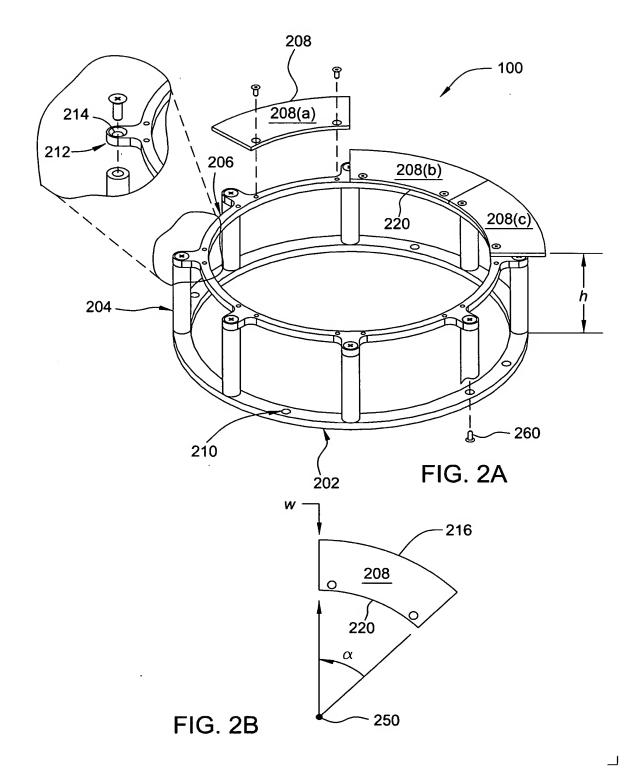
FIG.1

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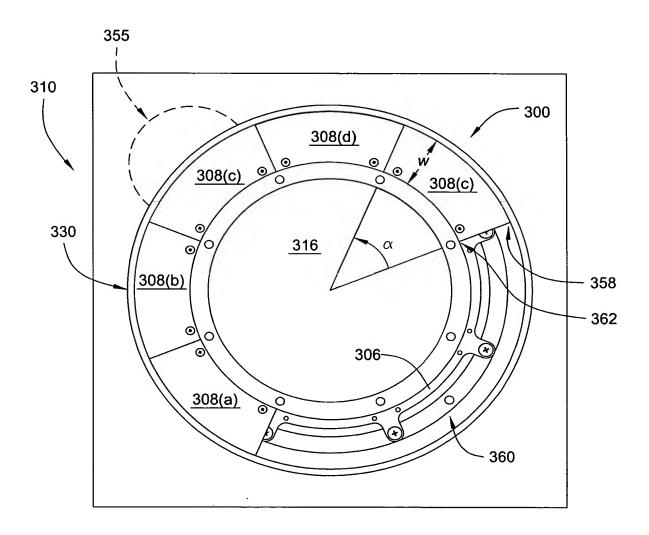
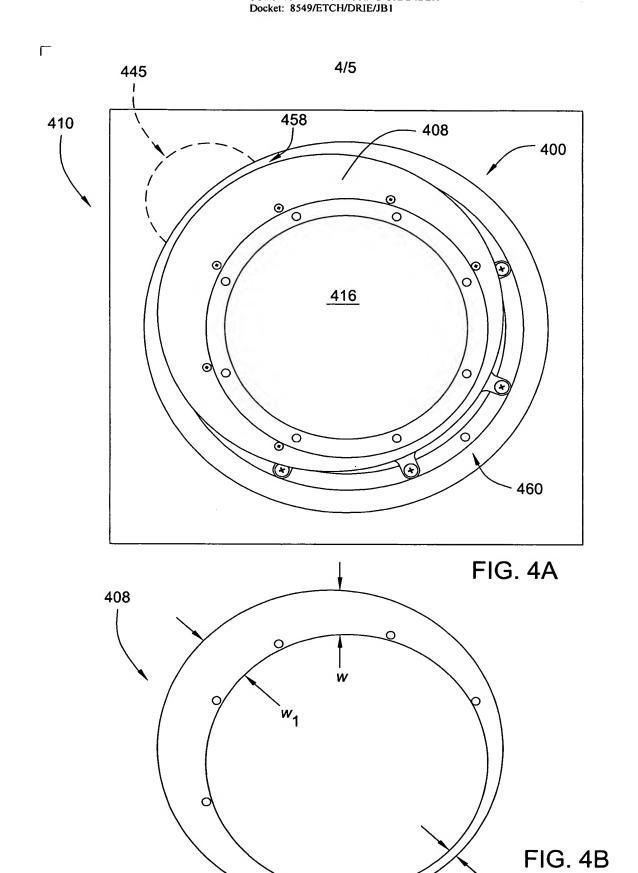


FIG. 3

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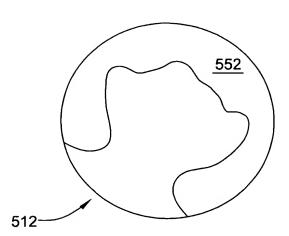


FIG.5A

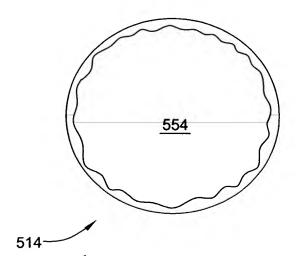


FIG.5B

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